

ABSTRACT

In a substrate treatment apparatus, a substrate to be treated (11) held on a substrate chuck section (13) is spun, and a plurality of treatment solutions are supplied onto the substrate to be treated (11). The apparatus has a plurality of collection tanks (16 to 19) provided to collect by kind the treatment solutions, scattered by a spin unit (15) from the substrate to be treated (11). To collect the treatment solution by one of the collection tanks, a lifting mechanism (28) is driven so that the treatment solution is collected with an inlet of only the collection tank opened, thereby preventing the treatment solution to be collected from mixing into the other collection tanks.